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8.1.3 Implantation of Primary Ions

Sommario/riassunto

Surveying and comparing all techniques relevant for practical applications, this second edition of a bestseller is a vital guide to this hot topic in nano- and surface technology. Completely revised and updated, sections include electron, ion and photon detection, as well as scanning microscopy, while new chapters have been added to cover such recently developed techniques as SNOM, SERS, and laser ablation. Over 500 references and a list of equipment suppliers make this a rapid reference for materials scientists, analytical chemists, and those working in the biotechnological industry.